

PATENT ABSTRACTS OF JAPAN(11)Publication number : **2002-332568**(43)Date of publication of application : **22.11.2002**

(51)Int.Cl.

C23C 14/34**C22C 5/06****G11B 7/24****G11B 7/26**(21)Application number : **2001-138674**(71)Applicant : **ISHIFUKU METAL IND CO LTD**(22)Date of filing : **09.05.2001**(72)Inventor : **HASEGAWA KOICHI****ISHII NOBUO****ASAKI TOMOMI****(54) SPUTTERING TARGET MATERIAL**

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a sputtering target material composed of Ag alloy and having high reflectivity and excellent sulfidation resistance.

SOLUTION: The sputtering target material is composed of the Ag alloy which is prepared by adding specific small amounts of metal component (A) selected from Ge, Ga and Sb, specific small amounts of metal component (B) selected from Au, Pd and Pt, and, if necessary, a small amounts of Cu to Ag and carrying out alloying.

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[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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